

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L11	1	("5409783").PN.	USPAT; USOCR	OR	OFF	2005/09/01 05:50
L19	33946	c08j005\$.ipc.	JPO	OR	ON	2005/09/01 06:40
L20	125742	g02f001\$.ipc.	JPO	OR	ON	2005/09/01 06:41
L22	158907	19 20	JPO	OR	ON	2005/09/01 06:41
L23	0	22 and electrode and sacrific\$5 and organic and conduct\$5	JPO	OR	ON	2005/09/01 06:42
L24	1	22 and electrode and sacrific\$5 and organic	JPO	OR	ON	2005/09/01 06:43
L25	3	22 and sacrific\$5 and organic	JPO	OR	ON	2005/09/01 06:43
L26	224	22 and nano\$9	JPO	OR	ON	2005/09/01 06:43
L27	9	22 and nano\$9 and gap	JPO	OR	ON	2005/09/01 06:43
S1	23	(electron near5 beam) same (etch\$4 with polymer\$4 with pattern\$4) same (molecular nano\$9)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:05
S2	31	((electron near5 beam) radiation) same (etch\$4 with polymer\$4 with pattern\$4) same (molecular nano\$9)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:06
S3	36	((electron near5 beam) radiation laser) same (etch\$4 with polymer\$4 with pattern\$4) same (molecular nano\$9)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:07
S5	1906	b23k015\$.ipc.	JPO	OR	ON	2005/08/31 13:08
S6	78230	(nano\$9 molecu\$5) and etch\$4 and (polymer\$4 pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:11
S7	1	S6 and S5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:10
S8	675457	(nano\$9 molecu\$5) and (polymer\$4 pattern\$4) not S7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:11

S9	1	S8 and S5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:28
S10	0	S5 and (sacric\$7 with layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:29
S11	0	S5 and sacric\$7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:29
S12	0	S5 and (sacrific\$4 with layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:30
S13	0	S5 and sacrific\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:30
S14	1906	S5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:30
S15	1	S5 and (etch\$5 and (organic molecul\$3) and conduct\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:33
S16	5506	adsorb\$ with electrode	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:33
S17	422	adsorb\$ with electrode with molecul\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:34
S18	7	(adsorb\$ with electrode with molecul\$5) and (remov\$5 with sacrific\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:41

S19	1	(adsorb\$ with electrode with molecul\$5) and ((remov\$5 with sacrific\$5) same (eb electron beam radiation laser))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 13:37
S20	1	("6306740").PN.	USPAT; USOCR	OR	OFF	2005/08/31 13:37
S21	72	(adsorb\$ with electrode with molecul\$5) and ((remov\$5 sacrific\$5) with layer\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:22
S22	189	204/486.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:23
S23	618	205/122.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:23
S24	2583	216/2,39,40,56,66,72.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:23
S25	2637	313/504.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:24
S26	1438	438/48,99.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:24
S27	2597	250/492.3.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:24
S28	10014	S22 S23 S24 S25 S26 S27	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:24
S29	1618	S28 and (conduct\$4 with organic\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:25

S30	601	S28 and ((conduct\$4 with organic\$5) with electrode)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:25
S31	670	S28 and ((conduct\$4 with organic\$5) with (electrode pattern\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:26
S32	139	S31 and (nano nano\$15)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/31 15:30
S33	45	S32 and ((remov\$4 etch\$5) with (pattern\$5 trace polymer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 06:26
S34	12	S32 and (((remov\$4 etch\$5) with (pattern\$5 trace polymer)) and ((remov\$4 etch\$5) with (electron beam laser)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/01 05:50